ASMMC.059GEN

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

MAR 1 5 2004 B

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App. No. : See Appendix A

Filed : See Appendix A

For : See Appendix A

Examiner : Unknown

ESTABLISHMENT OF RIGHT OF ASSIGNEE TO TAKE ACTION AND REVOCATION AND POWER OF ATTORNEY

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

The undersigned is empowered to act on behalf of the assignee below (the "Assignee") with regard to the issued U.S. Patents and the U.S. Patent Applications listed on Appendix A, attached hereto. For each patent or patent Application listed in Appendix A the original Assignment(s) from the Inventors to ASM Microchemistry OY is recorded at the Reel and Frame numbers indicated or is attached. A true copy of the original Assignment of all listed patents and patent applications from ASM Microchemistry OY to the Assignee is also attached hereto and was submitted to the Assignment Division of the Office on December 17, 2003. This represents the entire chain from the Inventor(s) to the Assignee.

I declare that all statements made herein are true, and that all statements made upon information and belief are believed to be true, and further, that these statements were made with the knowledge that willful, false statements and the like so made are punishable by fine or imprisonment, or both, under 18 U.S.C. § 1001, and that willful, false statements may jeopardize the validity of the application, or any patent issuing thereon.

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The undersigned hereby revokes any previous powers of attorney in the subject application, and hereby appoints the registrants of Knobbe, Martens, Olson & Bear, LLP, 2040 Main Street, Fourteenth Floor, Irvine, California 92614, Telephone (949) 760-0404, Customer No. 20,995, as its attorneys with full power of substitution and revocation to prosecute this application and to transact all business in the U.S. Patent and Trademark Office connected herewith. This appointment is to be to the exclusion of the inventor(s) and his attorney(s) in accordance with the provisions of 37 C.F.R. § 3.71.

Please use Customer No. 20,995 for all communications.

ASM INTERNATIONAL N.V.

Dated: 18 Feb. 2004

Menso Hendriks

Title: Central IP Officer

Address: Jan van Eycklaan 10

3723 BC Bilthoven THE NETHERLANDS

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App. No. Filed See Appendix A See Appendix A

APPENDIX A

App. No.	Filing Date	Attorney Docket No.	Title	Patent No.	Assignment
					from
8 90	30		196	em to the last	Inventors to
, ,				R. L.	ASM
3 6 30 3			· · · · · · · · · · · · · · · · · · ·	the second	Microchem.
	, , , , , ,	W			Reel/Frame
09/686,613	1/4/00	SEPP1.001CP1	METHOD AND APPARATUS FOR	6,630,030	011650/0441
,			GROWING THIN FILMS		
09/581,020	6/7/00	SEPP2.001APC	METHOD FOR COATING INNER	6,416,577	010951/0586
,			SURFACES OF EQUIPMENT		
09/619,820	7/20/00	SEPP4.001AUS	METHOD FOR REMOVING	6,506,352	011694/0504
			SUBSTANCES FROM GASES		
09/687,355	10/13/00	SEPP5.001AUS	METHOD FOR GROWING THIN	6,632,279	011557/0134
			OXIDE FILMS		
09/749,339	12/27/00	SEPP6.001AUS	APPARATUS FOR GROWING THIN	6,551,406	011670/0177
			FILMS		
09/749,329	12/27/00	SEPP7.001AUS	APPARATUS FOR GROWING THIN	6,447,607	011670/0191
			FILMS	·	
09/764,692	1/18/01	SEPP8.001AUS	PROCESS FOR GROWING	6,599,572	011484/0029
			METALLOID THIN FILMS UTILIZING		
			BORON-CONTAINING REDUCING		•
			AGENTS		
09/835,737	4/16/01	SEPP10.001AUS	PROCESS FOR PRODUCING OXIDE	6,548,424	012167/0702
			THIN FILMS		
09/800,757	3/6/01	ASMMC.002AUS	METHOD OF FORMING GRADED	6,534,395	011798/0754
			THIN FILMS USING ALTERNATING		
			PULSES OF VAPOR PHASE		
			REACTANTS		
09/843,518	4/26/01	ASMMC.004AUS	PROTECTIVE LAYERS PRIOR TO	6,482,733	011766/0345
			ALTERNATING LAYER DEPOSITION		
09/791,167	2/22/01	ASMMC.007AUS	METHOD OF FORMING ULTRATHIN	6,492,283	011953/0233
			OXIDE LAYER		
09/568,077	5/10/00	ASMMC.012AUS	APPARATUS FOR FABRICATION OF	6,562,140	011053/0323
			THIN FILMS		
09/769,562	1/25/01	ASMMC.012C1	APPARATUS FOR FABRICATION OF	6,579,374	011053/0323
			THIN FILMS		
09/687,204	10/13/00	ASMMC.026AUS	DEPOSITION OF TRANSITION	6,482,262	011505/0816
			METAL CARBIDES		
09/687,205	10/13/00	ASMMC.027AUS	PRODUCTION OF ELEMENTAL THIN	6,475,276	011505/0800
			FILMS USING A BORON-		
			CONTAINING REDUCING AGENT		

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					from
	- P. Same		Man Charles Committee Committee	1171 F. A. State J. L. X. S. C.	Inventors to:
8 .					ASM.
	A Section 1				Microchem.
1. 15 . 36 13		The Contract of the Contract o	in the result of the second control of the s	nigas kanala serakanah	Reel/Frame
10/205,296	7/24/02	SEPP4.001C1	METHOD AND APPARATUS FOR	Pending	011694/0504
			REMOVING SUBSTANCES FROM		/

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App. No.	Filing Date	Attorney Docket No.	<u>Title</u>	Patent No.	Assignment
					from 4.4
			9 9,3		Inventors to
	: " `	*		, 12 · 3	ASM .
		1 × 4 × 1			Microchem. Reel/Frame
	٠ .	1	GASES		Recorraine
10/618,429	7/10/03	SEPP5.001C1	METHOD FOR GROWING THIN	Pending	011557/0134
10/010,429	7710703	SET 13.001C1	OXIDE FILMS	Toname	01133770134
10/365,926	2/13/03	SEPP6.001DV1	APPARATUS FOR GROWING THIN	Pending	011670/0177
20.22.			FILMS		
10/205,297	7/24/02	SEPP7.001DV1	APPARATUS FOR GROWING THIN	Pending	011670/0191
			FILMS		
10/394,309	3/20/03	SEPP8.001C1	PROCESS FOR GROWING METAL	Pending	011484/0029
			OR METAL CARBIDE THIN FILMS		
			UTILIZING BORON-CONTAINING		
00/505.060	6/20/04	CEPPO COLLARG	REDUCING AGENTS		
09/787,062	6/28/01	GETT9.001APC	METHOD FOR GROWING UXIDE	Pending	011938/0097
			THIN FILMS CONTAINING BARIUM AND STRONTIUM		
09/836,674	4/16/01	SEPP11.001AUS	METHOD AND APPARATUS OF	Pending	012088/0322
05/050,074	4710701	SETT TI.OUTNES	GROWING A THIN FILM ONTO A	Tonding	012000/0522
			SUBSTRATE		
10/270,745	10/11/02	SEPP11.001CP1	METHOD AND APPARATUS OF	Pending	012088/0322
ŕ			GROWING A THIN FILM		
09/835,931	4/16/01	SEPP12.001AUS	METHOD OF GROWING A THIN	Pending	012029/0763
			FILM ONTO A SUBSTRATE		
09/854,706	5/14/01	SEPP14.001AUS	METHOD AND APPARATUS FOR	Pending	011811/0406
1			FEEDING GAS PHASE REACTANT		
10/000 510	10/20/04	0777745 004 1770	INTO A REACTION CHAMBER		010060/0054
10/003,749	10/23/01	SEPP15.001AUS	PROCESS FOR PRODUCING	Pending	012360/0374
			ALUMINUM OXIDE FILMS AT LOW TEMPERATURES		
10/066,315	1/29/02	SEPP16.001AUS	PROCESS FOR PRODUCING METAL	Pending	012950/0394
10/000,515	1/25/02	SELL TO.OUTAOD	THIN FILMS BY ALD	1 chang	012/30/03/4
10/067,634	2/4/02	SEPP17.001AUS	METHOD OF DEPOSITING RARE	Pending	012573/0185
			EARTH OXIDE THIN FILMS		and
					012913/0230
10/100,500	3/15/02	SEPP18.001AUS	METHOD FOR PREPARING METAL	Pending	012711/0064
			NITRIDE THIN FILMS		
10/110,598	4/11/02	SEPP19.001APC	METHOD OF MODIFYING SOURCE	Pending	013027/0564
10/110 500	4/14/02	GERRAL AND LEG	CHEMICALS IN AN ALD PROCESS		0100000000
10/110,730	4/11/02	SEPP20.001APC	METHOD OF DEPOSITING	Pending	013038/0940
			TRANSITION METAL NITRIDE THIN FILMS		
10/148,525	8/27/02	SEPP21.001APC	METHOD OF GROWING OXIDE	Pending	013005/0964
10/170,323	0/2//02	SELIZI.OUIAI C	FILMS	i chang	013003/0304
10/276,663	11/15/02	SEPP22.001APC	PROCESS FOR PRODUCING	Pending	Сору
,			INTEGRATED CIRCUITS		Attached
10/333,521	1/17/03	SEPP23.001APC	METHOD OF GROWING A THIN	Pending	013967/0142
			FILM ONTO A SUBSTRATE	<u></u>	
10/253,859	9/23/02	ASMMC.002C1	GRADED THIN FILMS	Pending	011798/0754
10/329,658	12/23/02	ASMMC.002DV1	GRADED THIN FILMS	Pending	011798/0754
10/237,526	9/6/02	ASMMC.004DV1	PROTECTIVE LAYERS PRIOR TO	Pending	011766/034

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					<u>from</u>
					Inventors to
					ASM
L.				1 4/2	Microchem. Reel/Frame
		3.0	ALTERNATING LAYER DEPOSITION	<u> </u>	Recordance
10/303,355	11/21/02	ASMMC.4DV1C1	METHOD FOR CONTROLLING	Pending	011766/0345
10/303,333	11/21/02	ASMINIC.4D VICT	CONFORMALITY WITH	Tending	01170070545
			ALTERNATING LAYER DEPOSITION		
10/303,293	11/22/02	ASMMC.4DV1CP1	SEALING POROUS STRUCTURES	Pending	013888/0070
09/887,199	6/21/01	ASMMC.005AUS	METHOD OF FABRICATING	Pending	012472/0873
, , , , , , , , , , , , , , , , , , , ,			TRENCH ISOLATION STRUCTURES		
	1		FOR INTEGRATED CIRCUITS USING		
	1		ATOMIC LAYER DEPOSITION		
10/049,125	2/7/02	ASMMC.008APC	METHOD FOR DEPOSITING	Pending	013209/0629
			NANOLAMINATE THIN FILMS ON	:	*
	1		SENSITIVE SURFACES		
10/383,291	3/6/03	ASMMC.012C2	APPARATUS FOR FABRICATION OF	Pending	011053,0323
			THIN FILMS		
09/997,396	11/28/01	ASMMC.020AUS	THIN FILMS FOR MAGNETIC	Pending	012562/0145
			DEVICE		01150510015
10/246,131	9/17/02	ASMMC.026C1	DEPOSITION OF TRANSITION	Pending	011505/0816
10/010 71	- 12 0 / 0 0	100000000000000000000000000000000000000	METAL CARBIDES	D 1	011505/0000
10/210,715	7/30/02	ASMMC.027C1	PRODUCTION OF ELEMENTAL	Pending	011505/0800
			FILMS USING A BORON- CONTAINING REDUCING AGENT		
09/945,463	8/31/01	ASMMC.029AUS	METHODS FOR MAKING A	Pending	012303/0047
09/943,403	0/31/01	ASIMINIC.029AUS	DIELECTRIC STACK IN AN	Tending	012303/004/
			INTEGRATED CIRCUIT		
10/653,737	9/2/03	ASMMC.029DV1	METHODS FOR MAKING A	Pending	012303/0047
10,000,,0	// = // = //		DIELECTRIC STACK IN AN		
			INTEGRATED CIRCUIT		
09/801,542	3/7/01	ASMMC.030AUS	ALD REACTOR AND METHOD WITH	Pending	011610/0908
			CONTROLLED WALL		
			TEMPERATURE		
10/227,475	8/22/02	ASMMC.031AUS	LOW TEMPERATURE METHOD OF	Pending	013897/0346
	İ		FORMING A GATE STACK WITH A		
			HIGH K LAYER DEPOSITED OVER		
			AN INTERFACIAL OXIDE LAYER	7.	012660/0500
10/136,095	4/30/02	ASMMC.032AUS	METHOD OF DEPOSITING THIN	Pending	013660/0588
10/007 204	12/5/01	A CNANAC 022 A LIC	FILMS FOR MAGNETIC HEADS COPPER INTERCONNECT	Pending	012874/0783
10/007,304	12/5/01	ASMMC.033AUS	STRUCTURE HAVING STUFFED	rending	012874/0783
			DIFFUSION BARRIER		
10/066,169	1/30/02	ASMMC.034AUS	ACTIVE PULSE MONITORING IN A	Pending	012570/0319
10/000,109	1/30/02	AUDIVIDUO-03-AUS	CHEMICAL REACTOR	Tonding	101237070319
10/187,142	6/28/02	ASMMC.035AUS	SOURCE CHEMICAL CONTAINER	Pending	013369/0749
10/10/,172	0.23,02	11011111010001100	ASSEMBLY		
09/975,466	10/9/01	ASMMC.036AUS	IN SITU REDUCTION OF COPPER	Pending	012382/0183
,,,,,			OXIDE PRIOR TO SILICON CARBIDE		and
			DEPOSITION		012644/0307
10/222,005	8/14/02	ASMMC.037AUS	ATOMIC LAYER DEPOSITION	Pending	013590/0973
			REACTOR		

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App. No.	Filing Date	Attorney Docket No.	<u>Title</u>	Patent No.	Assignment from Inventors to ASM Microchem. Reel/Frame
10/242,368	9/12/02	ASMMC.038AUS	METAL NITRIDE DEPOSITION BY	Pending	013590/0968
			ALD WITH REDUCTION PULSE		0.10.500.400.1.5
10/285,348	10/30/02	ASMMC.042AUS	METHOD OF MONITORING EVAPORATION RATE OF SOURCE	Pending	013788/0317
		_	MATERIAL IN A CONTAINER		

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